CLAIMS:

1. A method of creating a data storage disk master:

creating a plurality of three or more equally spaced and focused laser spots; and

simultaneously illuminating a photoresist layer of the master with the plurality of focused laser spots to photolithographically expose a plurality of tracks of the master.

2. The method of claim 1, further comprising creating the plurality of focused laser spots from a single laser by optically separating light from the laser into a plurality of light beams corresponding to the plurality of focused laser spots.

3. The method of claim 1, further comprising creating the plurality of focused laser spots using a plurality of different lasers.

4. The method of claim 1, wherein creating the plurality of focused laser spots comprises creating a one-dimensional array of focused laser spots.

5. The method of claim 1, wherein creating the plurality of focused laser spots comprises creating a two-dimensional array of focused laser spots.

6. The method of claim 1, further comprising simultaneously illuminating the photoresist layer of the master a plurality of times with the plurality of focused laser spots.

7. The method of claim 1, further comprising:

translating the plurality of focused laser spots relative to the photoresist layer by an integer number of the tracks; and

simultaneously illuminating the photoresist layer of the master with the plurality of focused laser spots to photolithographically expose a different plurality of tracks of the master.

8. The method of claim 7, further comprising:

repeatedly translating the plurality of focused laser spots relative to the photoresist layer by the integer number of the tracks over substantially an entire surface of the master; and

repeatedly simultaneously illuminating the photoresist layer of the master with the plurality of focused laser spots over substantially the entire surface of the master.

9. The method of claim 8, wherein track pitch variations on the master are less than five nanometers.

10. The method of claim 7, wherein the master defines a track width equal to a distance between each of the plurality of focused laser spots.

11. The method of claim 7, wherein the master defines a track width less than a distance between each of the plurality of focused laser spots.

12. A method of creating a data storage disk master:

creating an interference pattern from laser light, the interference pattern defining a plurality of constructive interference fringes; and

simultaneously illuminating a photoresist layer of the master with the plurality of constructive interference fringes of the interference pattern to expose a plurality of tracks of the master.

13. The method of claim 12, wherein creating the interference pattern comprises creating an interference pattern that includes the plurality of constructive interference fringes in a one-dimensional array.

14. The method of claim 12, wherein creating the interference pattern comprises creating an interference pattern that includes the plurality of constructive interference fringes in a two-dimensional array.

15. The method of claim 12, further comprising creating the interference pattern using a prism.

16. The method of claim 12, further comprising simultaneously illuminating the photoresist layer of the master a plurality of times with the interference pattern.

17. The method of claim 11, further comprising:

translating the plurality of constructive interference fringes of the interference pattern relative to the photoresist layer by an integer number of the tracks; and

simultaneously illuminating the photoresist layer of the master with the interference pattern to expose a different plurality of tracks of the master.

18. The method of claim 17, further comprising:

repeatedly translating the plurality of constructive interference fringes of the interference pattern relative to the photoresist layer by an integer number of the tracks over substantially an entire surface of the master; and

repeatedly simultaneously illuminating the photoresist layer of the master with the interference pattern over substantially the entire surface of the master, wherein track pitch variations on the master are less than five nanometers.

19. The method of claim 17, wherein the master defines a track width equal to a distance between each of the plurality of constructive interference fringes of the interference pattern.

20. The method of claim 17, wherein the master defines a track width less than a distance between each of the plurality of constructive interference fringes of the interference pattern.